

REMARKS/ARGUMENTS

Favorable reconsideration of this application as presently amended and in light of the following discussion is respectfully requested.

Claims 1-11 and 37-340 are presently active; Claims 1, 6, and 11 having been amended, Claims 37-40 having been added, and Claims 12-36 having been canceled without prejudice or disclaimer. Support for the amendment to Claims 1, 6, and 11 is found, for example, in Fig. 3. Support for new Claims 37-39 is found, for example, in Figs. 3 and 5. Support for new Claim 40 is found, for example, in Fig. 4. Applicants respectfully submit that no new matter is added.

In the Office Action, Claims 1-3, 5-8, 10, and 11 were rejected under 35 U.S.C. §102(b) as anticipated by or, in the alternative, under 35 U.S.C. §103(a) as obvious over Kosugi et al. (U.S. Patent No. 6,197,116, hereinafter Kosugi); Claims 1-11 were rejected under 35 U.S.C. §102(e) as anticipated by, or in the alternative, obvious over Tanaka et al. (U.S. Patent No. 6,616,759, hereinafter Tanaka); and Claims 1-3, 5-8, 10, and 11 were rejected under 35 U.S.C. §102(b) as anticipated by or, in the alternative, under 35 U.S.C. §103(a) as obvious over Saxena (U.S. Patent No. 5,642,296).

Firstly, Applicants acknowledge with appreciation the courtesy of Examiner Kackar to interview this case on July 10, 2007 during which time the issues in the outstanding Office Action were discussed as substantially summarized hereinafter.

Secondly, as discussed during the interview, Applicants' Figure 3 shows a magnetic field system 60 disposed around process tool 10. Furthermore, as discussed during the interview, Applicants' Figure 5 shows inductive coil 80 disposed around process tool 10.

As discussed during the interview, neither Kosugi, Tanaka, nor Saxena disclose or suggest a magnetic field system disposed around the process tool or a inductive coil disposed around the process tool.

While no agreement on patentability was reached during the interview, these differences were pointed out as structural differences from Kosugi, Tanka, and Saxena. Accordingly, the present amendment presents these features for the examiner's formal consideration in independent Claims 1, 6, 11, and 39.

It is respectfully submitted that Kosugi, Tanaka, and Saxena fail to disclose or suggest "a magnetic field system disposed around the process tool and configured to increase plasma density" of Claims 1, 6, and 11 and "an inductive coil disposed around the process tool and configured to increase plasma density" of Claim 39.

Thus, Claims 1, 6, 11, and 39, and the claims dependent therefrom, are believed to patentably define over the art of record.

Furthermore, Applicants respectfully submit that new Claim 40 patentably defines over Tanaka, Kosugi, and Saxena. Tanka, Kosugi, and Saxena, taken alone or in proper combination, do not disclose or suggest the claimed

A material processing system comprising...

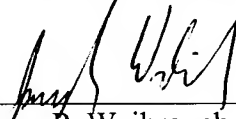
- a first electrode disposed within the process tool;
- a second electrode opposing the first electrode;
- a first RF generator coupled to the first electrode and configured to couple power at a first RF frequency; and
- a second RF generator coupled to the second electrode and configured to couple power at a second RF frequency,

wherein the second RF frequency is different than the first RF frequency.

Consequently, in view of the present amendment and in light of the above discussions, the outstanding grounds for rejection are believed to have been overcome. The application as amended herewith is believed to be in condition for formal allowance. An early and favorable action to that effect is respectfully requested.

Respectfully submitted,

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